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(71) Applicant (for all designated States except US): INFM IS-
TITUTO NAZIONALE PER LA FISICA DELLA MA-
TERIA [IT/IT]; Corso F. Perrone 24, I-16152 GENOVA
(IT).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **CAPUTO, Roberto**
[IT/IT]; Via Parigi 21, I-87036 RENDE (Cosenza) (IT).
UMETON, Cesare [IT/IT]; Via Tevere 68, I-87036
RENDE (Cosenza) (IT). **VELTRI, Alessandro** [IT/IT];
Via P. Borsellino - Fabbicato S.E.M., s.n., I-87100
COSENZA (IT). **SUKHOV, Andrey** [RU/RU]; pr.
Karamzina 9 - Apt. 60, MOSCOW, 117463 (RU).
TABIRYAN, Nelson [AM/US]; 809 South Orlando Av-
enue - Suite I, WINTER PARK, Florida 32789 (US).

(74) Agent: **RAMBELLI, Paolo**; Corso Regio Parco 27,
I-10152 TORINO (IT).

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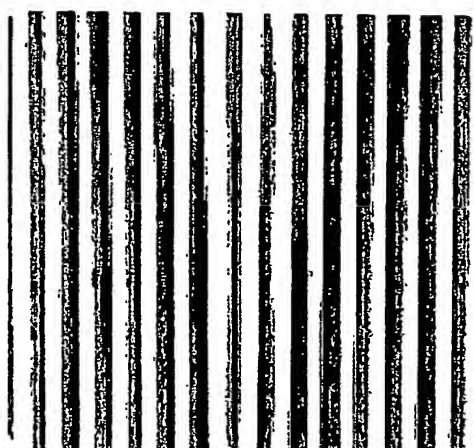
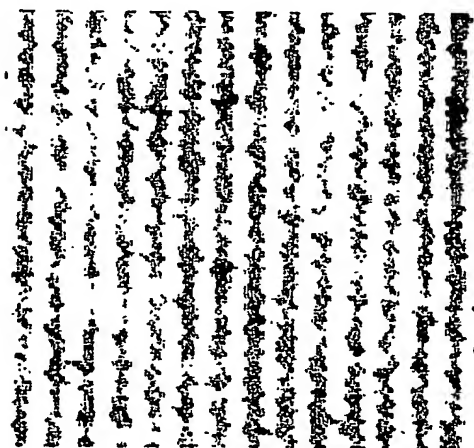
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[Continued on next page]

(54) Title: HOLOGRAPHIC DIFFRACTION GRATING, PROCESS FOR ITS PREPARATION AND ELECTRO-OPTICAL DE-
VICES INCLUDING THE SAME



(57) Abstract: Composite polymer/liquid crystal material having a holographic grating structure formed by an alternating ordered succession of crystal layers. The nematic liquid crystal manophasic region which is substantially free from furthermore, the holo-
graphic grating structure is comprises the steps of: -heating a mixture of a photoinitiator, a monomer Composite polymer/liquid
crystal material having a holographic grating structure of polymer layers and nematic liquid layers comprise an ordered nematic liq-
uid crystal droplets. obtained by a process which above the nematic/isotropic phase separation -illumination of -tion; -slow
cooling of transition and a nematic liquid crystal and the temperature, in order to prevent isotropic/nematic phase transition of the
liquid crystal; mixture at a rate lower than 0.3°C/mixture, to achieve a mixture with an interference pattern to induce polymerise the
complete orientation of the liquid crystal director, and below the isotropic/nematic transition temperature.

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